

Ken Collins

List of Publications by Year in descending order

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15
papers

357
citations

933447

10
h-index

996975

15
g-index

15
all docs

15
docs citations

15
times ranked

164
citing authors

#	ARTICLE	IF	CITATIONS
1	Self-organized pattern formation in radio frequency capacitively coupled discharges. Journal of Applied Physics, 2021, 129, .	2.5	5
2	On the scaling of rf and dc self-bias voltages with pressure in electronegative capacitively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, 021303.	2.1	9
3	Extraction of negative ions from pulsed electronegative capacitively coupled plasmas. Journal of Applied Physics, 2012, 112, .	2.5	32
4	Impact of Phase Shifted Coil Currents on Plasma Uniformity. IEEE Transactions on Plasma Science, 2011, 39, 2516-2517.	1.3	5
5	Recouping etch rates in pulsed inductively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2011, 29, .	2.1	22
6	Tailoring Ion Energy Distributions Using Pulsed Plasmas. IEEE Transactions on Plasma Science, 2011, 39, 2520-2521.	1.3	4
7	Effect of resonance in external radio-frequency circuit on very high frequency plasma discharge. Journal of Applied Physics, 2010, 107, .	2.5	31
8	Influence of inhomogeneous magnetic field on the characteristics of very high frequency capacitively coupled plasmas. Journal of Applied Physics, 2010, 107, 053302.	2.5	23
9	Plasma-Profile Control Using External Circuit in a Capacitively Coupled Plasma Reactor. IEEE Transactions on Plasma Science, 2010, 38, 3241-3248.	1.3	7
10	Three-dimensional model of magnetized capacitively coupled plasmas. Journal of Applied Physics, 2009, 105, .	2.5	27
11	Effect of azimuthally asymmetric reactor components on a parallel plate capacitively coupled plasma. Journal of Applied Physics, 2009, 106, .	2.5	10
12	Synchronous Pulse Plasma Operation upon Source and Bias Radio Frequencies for Inductively Coupled Plasma for Highly Reliable Gate Etching Technology. Japanese Journal of Applied Physics, 2009, 48, 08HD01.	1.5	28
13	Effect of simultaneous source and bias pulsing in inductively coupled plasma etching. Journal of Applied Physics, 2009, 106, .	2.5	48
14	Self-consistent simulation of very high frequency capacitively coupled plasmas. Plasma Sources Science and Technology, 2008, 17, 035003.	3.1	84
15	Control of Plasma Uniformity Using Phase Difference in a VHF Plasma Process Chamber. IEEE Transactions on Plasma Science, 2008, 36, 1366-1367.	1.3	22